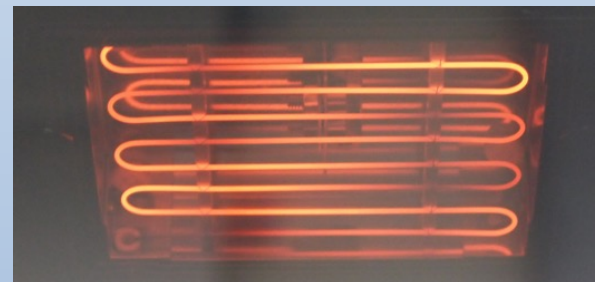
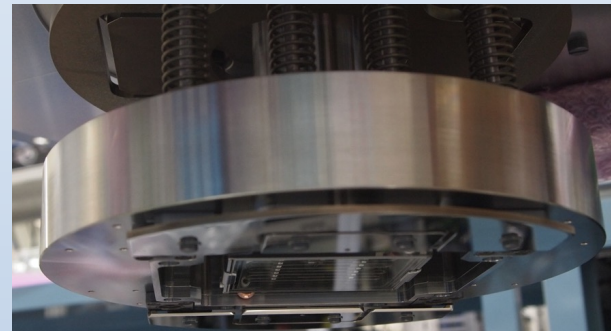
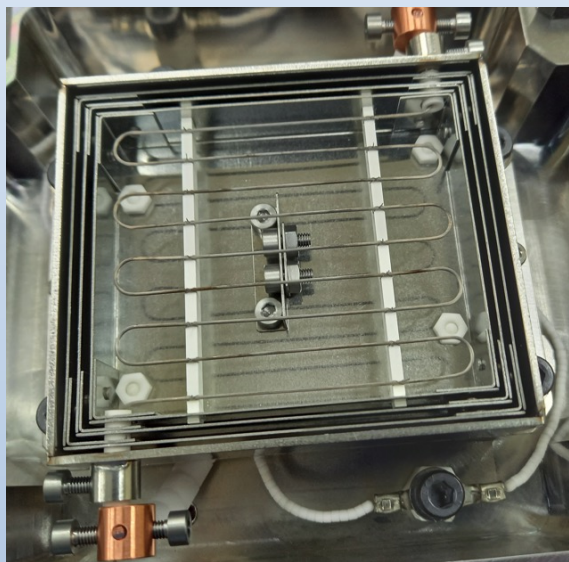


# Sharing innovation moments with **vacuum technology** & **glove box technology**

## General purpose **high temperature heating mechanism**

It is possible to control substrate high temperature heating during film formation by installing it in evaporation system , sputtering system, etc.

Useful for evaluation of crystallinity, arrangement, modification, etc.



### Specifications

Item	Specification	Remarks
Heating temperature	~600°C	Temperature monitor value
Effective heating area	約40mm × 40mm	
Heater material	Tungsten	With a quartz plate shield
Heater capacity	20V,20A	Approximately 10V-11A at 500°C
Temperature monitor	K type thermocouple	Type changeable
Usage environment	Vacuum (less than $7 \times 10^{-2}$ Pa)	

### Option

~900°C specification / Various susceptors / Substrate trays / etc

Dimension

